

GENERAL PROCESS AND OPERATION SPECIFICATION

Corial PlasmaTherm Fluorine

I. SCOPE

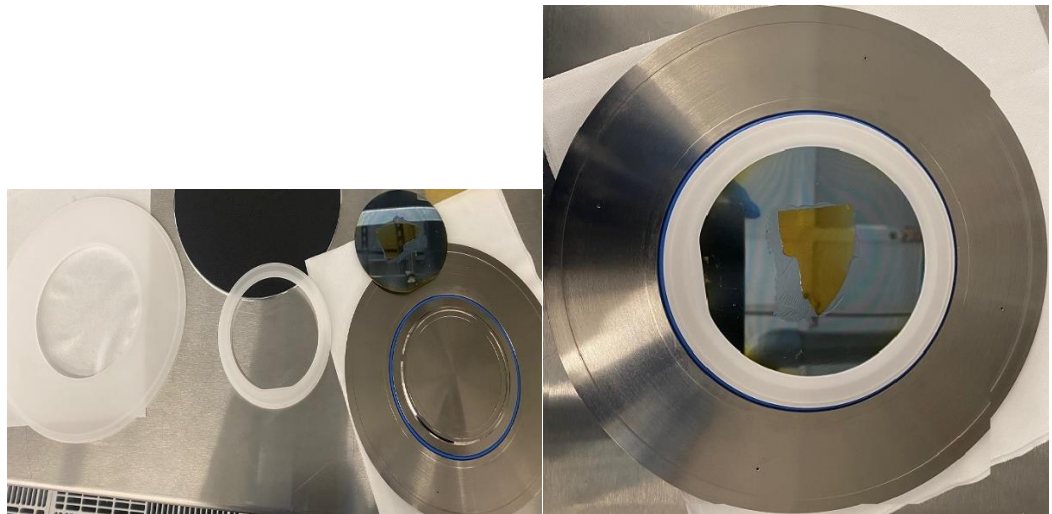
The purpose of this document is to describe the requirements and basic operating instructions for Corial PlasmaTherm Fluorine. This tool is intended for general purpose use to etch Si substrate and the films of SiO_2 and Si_3N_4 . It can process the substrate ranging from small pieces to 8-inch.

II. SAFETY

- a. You must be trained and signed off to use this equipment.
- b. If you are unsure about any procedure or indication while operating this equipment, contact a staff member or trainer for assistance.

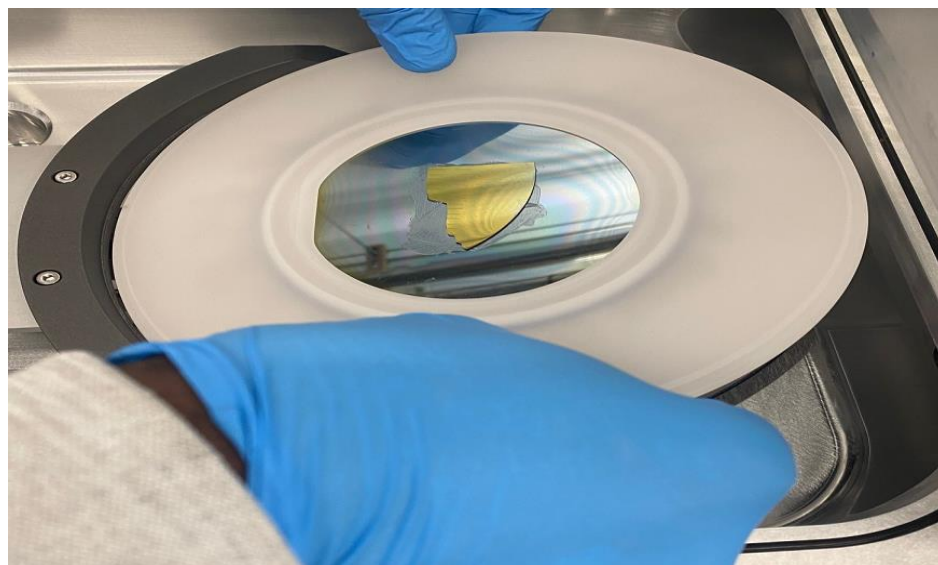
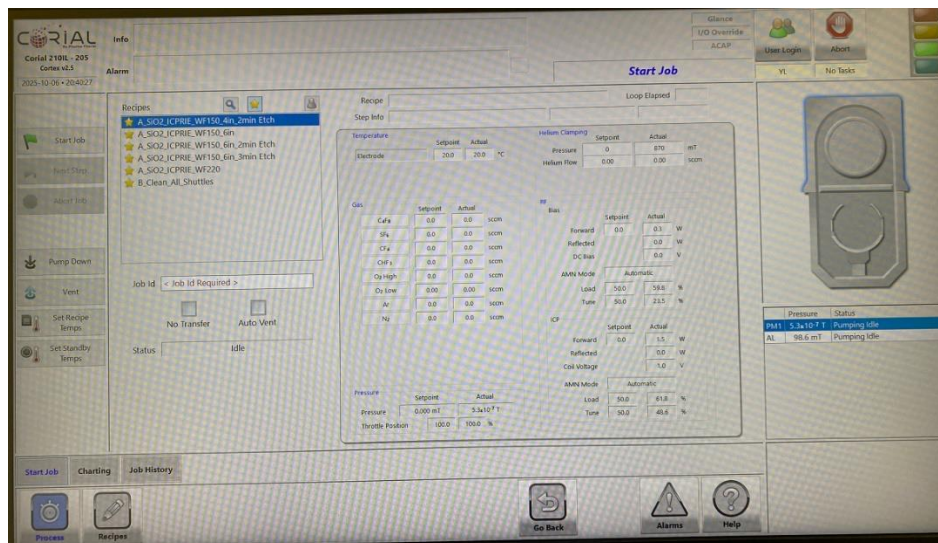
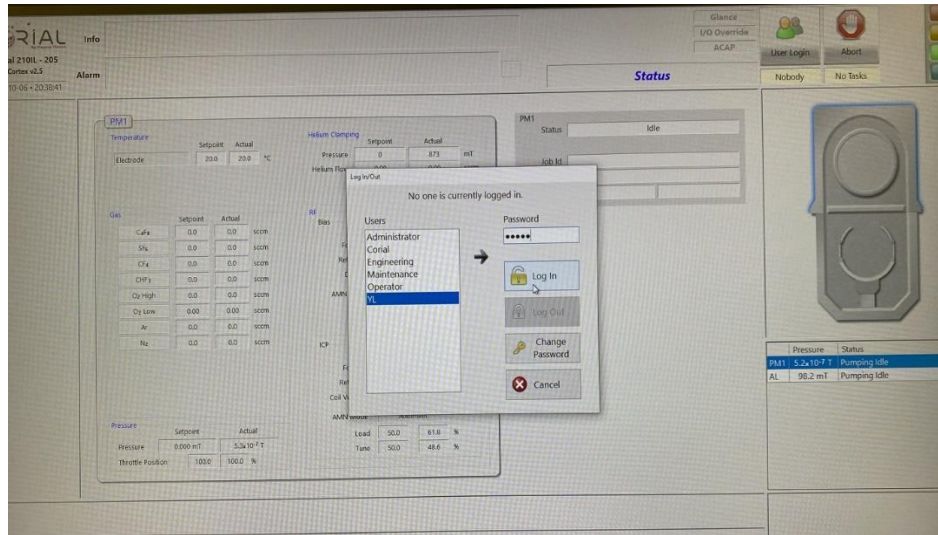
III. OPERATION

1. Start the iLab connection.
2. If you process small pieces, please use crystal bond to stick the pieces to 4-inch carrier.
3. Take the quartz clamps and metal plate from the box
4. Be careful to use the quartz clamps to hold wafer onto the metal plate.



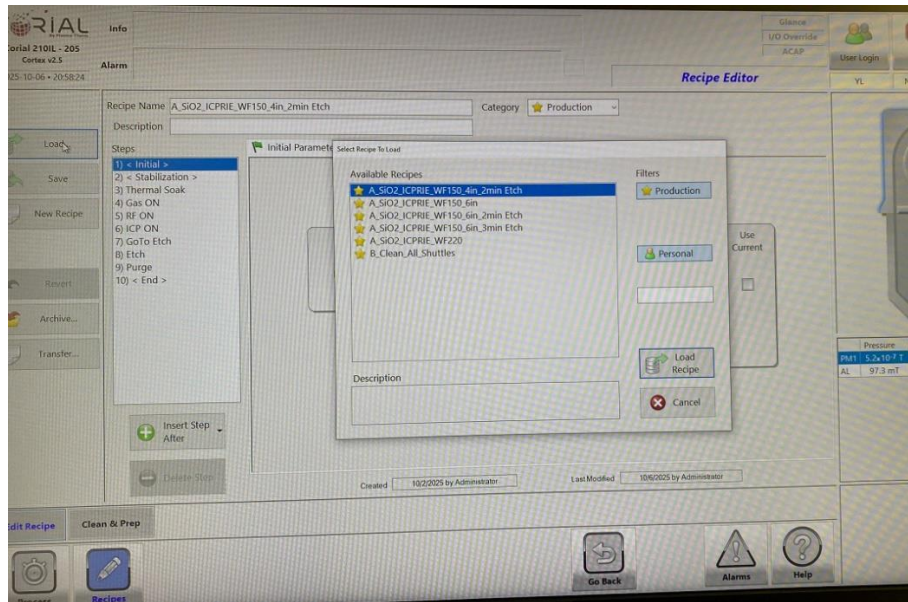
5. In the monitor, click on “User Login”, select username, input “Password”, and click on “Log In”
6. Click on “Vent”, wait for the “Status” to become “Venting Idle”

- Open the load lock, be careful to load the metal plate onto the shuttle.

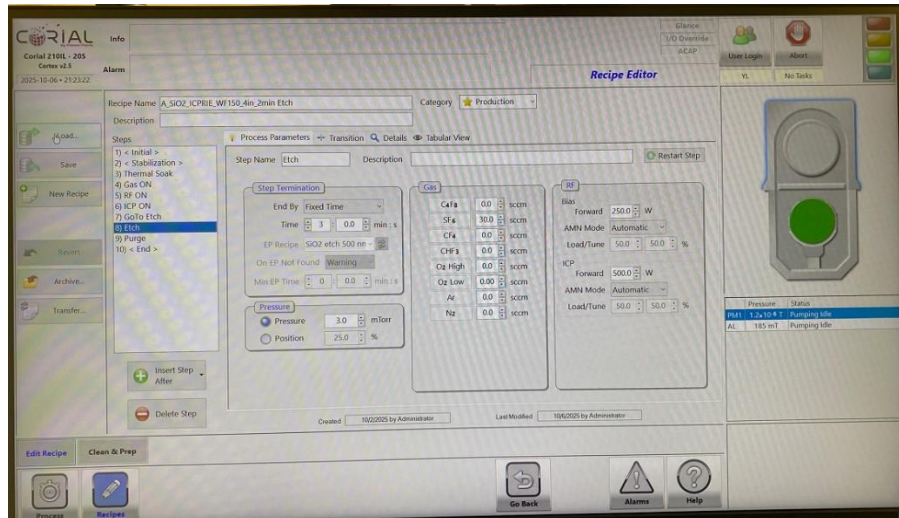


Corial PlasmaTherm Fluorine

- Close the load lock, and then click on “Pump Down”. You may select “Auto Vent”.
- Click on “Recipes”, choose the recipe and click on “Load Recipe”.

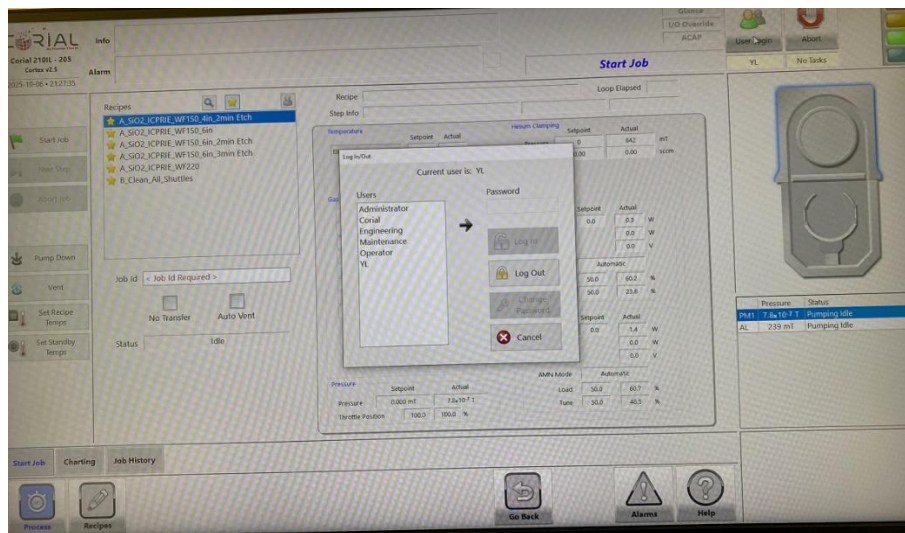
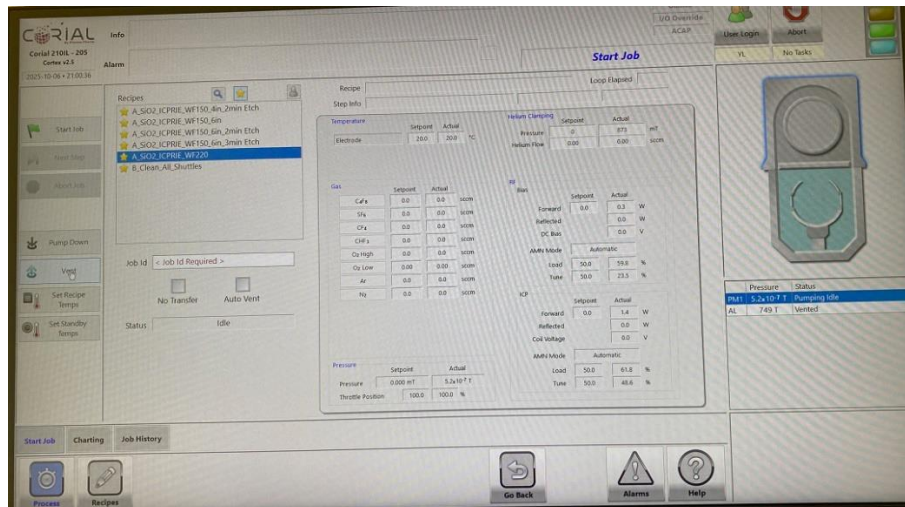


- You can change the recipe parameters and click on “Save” to save the change.



- Click on “Process” and then click on “Start Job”.
- Wait for the etch to complete.
- Click on “Vent” to open the load lock.
- Be careful to remove the metal plate from the shuttle.
- Close the load lock, click on “Pump Down” to pump down it.
- Click on “User Login” and then click on “Log Out”.
- Be careful to remove the wafer from the metal plate.
- Return the quartz clamps and metal plate to the box.

Corial PlasmaTherm Fluorine



- 19. Fill out the log sheet.
- 20. Stop the iLab connection.

Approvals:

Technical Manager Signature: Sandra G Malhotra

Date: 10/08/2025

Revision History:

Revision	Author	Date
Original Issue	Yaguang Lian	08 October 2025